Attorney Docket: 155/506

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

KIYOSHI DEMIZU ET AL

Serial No.:

Not Yet Assigned

Group Art Unit:

Filed:

December 27, 2001

Examiner:

CAM#: 29368.029

Title:

SEMICONDUCTOR WAFER AND DEVICE SEMICONDUCTOR

DEVICE MANUFACTURING PROCESS

PRELIMINARY AMENDMENT

Box PCT

To the Assistant Commissioner

for Patents

Washington, D.C. 20231

Sir:

Preliminary to examination of the above-captioned PCT national stage application, kindly amend the application as follows:

In the claims:

Please cancel claims 1 through 16, inclusive, without prejudice or disclaimer and substitute therefor the following new claims 17 through 35:

- 17. (New) A semiconductor wafer having a roughness of the backside surface varied in a direction of a radius, wherein varied sections exist substantially coaxially in the direction of the radius.
- 18. (New) A semiconductor wafer having a roughness of the backside surface varied in a direction of a radius, wherein sections of the different

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